

**Notice of References Cited**Application/Control No.  
10/604,651Applicant(s)/Patent Under  
Reexamination  
PENG ET AL.Examiner  
Alexander G. GhykaArt Unit  
2812

Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	L	US-			
	M	US-			

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**NON-PATENT DOCUMENTS**

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Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.

  
2/15/07